CVD 1033 - Tube 2 - Nitride Deposition Rate
Si3N4 deposited on 4" n-type, (100) Si @ 780 °C, 300 mT, NH3 = 100 sccm, DCS = 10 sccm, 40 min

- Refractive index: 1.99
- Thickness nonuniformity < 3%